

Tool ID: 801  
Tool Location: 224

Equipment Information Sheet

# Logitech Orbis CMP

**Manager: Christopher Alpha 607-254-4913**

**Backup: Michael Skvarla 607-254-4674**

**Backup: Sam Wright 607-254-4836**

Calls to staff phones will be automatically forwarded to their cell phones during accessible hours. At other times leave a message or send them an email.

**SAFETY**

**USAGE RESTRICTIONS**

**SCHEDULING/SIGN-UP RESTRICTIONS**

Minimum Tool Time: 30 minutes

- None

**MATERIALS COMPATIBILITY CATEGORY**

| Tool Category 2: Silicon Based Substrates and Select Refractory Metals |                                                                                                                    |
|------------------------------------------------------------------------|--------------------------------------------------------------------------------------------------------------------|
| Allowed                                                                | Not Allowed                                                                                                        |
| Tool category 1/1E materials                                           | No Glass Substrates                                                                                                |
| Silicon Based Materials only                                           | No CNF Class A or Class B metals and oxides/compounds of (exposed or buried) (ie Magnesium, Zinc, Barium, Calcium) |
| Si, SiC, SiO <sub>2</sub> substrates                                   |                                                                                                                    |
| All Furnace grown or deposited films                                   |                                                                                                                    |
| PECVD Films                                                            | No Gold, Silver or Copper (Exposed or buried)                                                                      |
| ALD dielectric films                                                   | No High Vapor pressure materials                                                                                   |
| CNF Refractory Metals (ie Al, Ti,Ta,W,Pt,Mo,Cr,Ni)                     | No III/V Compound Semiconductors                                                                                   |
| Nitrides and Oxides of above metals                                    | No Organic/Biology Molecules prepared-with or without Salt buffers                                                 |
| Cured organics and baked Photoresist                                   |                                                                                                                    |

High Vapor Pressure Metals and Compounds are materials that have a vapor pressure above 1e-6 Torr at 400 C.

**Additional Material Restrictions and Exceptions**

- 4 and 6 Wafers (pieces possible)
- Wafers must not be excessively thin or thick
- No GaAs

Last Updated: 06/18/2025